L Number	Hits	Search Text	DB	Time stamp
1	44	((mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/17 10:30
		(before or prior) with (exposur\$3 or lithograph\$6 or photomask\$3 or	US-PGPUB;	
		photo-mask\$3 or mask\$3 or resist or photo-resist or photolithograph\$6	EPO; JPO;	
		or stepper or photo-lithograph\$6)) and (photomask\$3 or photo-mask\$3	DERWENT;	
		or photoresist or photo-resist or ((mask\$3 or resist) with (photo or EUV or UV or ultra-violet or light or DUV or excimer or lightsource or	IBM_TDB	
	·	photolithograph\$6 or photosensit\$6 or photo-lithograph\$6 or positive or		
		negative)))		
2	56	(mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/17 07:19
~	50	(deposit\$4 or anneal\$5).clm.	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
3	333	(mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/17 07:20
		(deposit\$4 or anneal\$5) with (advantag\$5 or cost)	US-PGPUB;	
			EPO; JPO;	
			DERWENT; IBM TDB	
4	226	(mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/17 10:31
4	326	(deposit\$4 or anneal\$5) with (advantag\$5 or cost)	US-PGPUB;	200 110717 10.51
		(deposit 4 of annear 5) with (advantages of cost)	EPO; JPO;	
			DERWENT;	
			IBM TDB	
5	349136	700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls.	USPAT;	2004/09/17 12:00
			US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	2004/00/17 07:21
6	59	((mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/17 07:21
		(deposit\$4 or anneal\$5) with (advantag\$5 or cost)) and (700/\$.ccls. or	US-PGPUB; EPO; JPO;	
		702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls.)	DERWENT;	
			IBM TDB	
20	24121	(photomask\$3 or photo-mask\$3 or mask\$3) near3 (type or kind or class)	USPAT;	2004/09/17 10:31
20	27121	(photomaskes of photo maskes) now (type 1	US-PGPUB;	
			ЕРО, ЛРО;	
			DERWENT;	
			IBM_TDB	
21	1577	(photomask\$3 or photo-mask\$3 or mask\$3) near3 (type or kind or	USPAT;	2004/09/17 10:58
		class).clm.	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT; IBM_TDB	
22	072	(700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls.)	USPAT;	2004/09/17 10:31
22	873	and ((photomask\$3 or photo-mask\$3 or mask\$3) near3 (type or kind or	US-PGPUB;	200 (10)/17 10:51
		class).clm.)	EPO; JPO;	
		class).cliff.)	DERWENT;	
			IBM_TDB	
23	473141	(mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) or	USPAT;	2004/09/17 10:32
		batch or lot	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
		The state of the s	IBM_TDB	2004/00/17 10:40
24	89		USPAT; US-PGPUB;	2004/09/17 10:40
		and ((photomask\$3 or photo-mask\$3 or mask\$3) near3 (type or kind or	EPO; JPO;	
		class).clm.)) and ((mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4	DERWENT;	
ų.		or making)) or batch or lot)	IBM_TDB	
			רות "ואותו	

T 2 "	10.0	T 0 0 0 0 0 0 0 0 0 0 0 0 0 0 0 0 0 0 0	TIODATE	1 200 1 100 11 2 10 10
25	1063	257/390.ccls.	USPAT;	2004/09/17 10:40
	1		US-PGPUB;	
1			ЕРО; ЛРО;	
	[		DERWENT;	
			IBM_TDB	
26	58	257/390.ccls. and (organic or polymer or resin or polyimide or phenolic	USPAT;	2004/09/17 10:42
}	ļ	or acrylic)	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
27	25472	(photomask\$3 or photo-mask\$3 or mask\$3) near3 (type or kind or class	USPAT;	2004/09/17 10:59
		or (metal and (organic or polymer or resin or polyimide or phenolic or	US-PGPUB;	
	]	acrylic)))	ЕРО; ЛРО;	
	1		DERWENT;	
			IBM_TDB	1
28	7786	(photomask\$3 or photo-mask\$3 or mask\$3) with (metal and (organic or	USPAT;	2004/09/17 12:04
20	7760	polymer or resin or polyimide or phenolic or acrylic))	US-PGPUB;	2004/03/17 12:04
ļ	]	polyther of resit of polythilde of phenotic of actyric))	EPO; JPO;	
			DERWENT;	
	1		IBM_TDB	
29	307	((nhatawaght)) an mhata maght) an maght) nam? (time an lind or along	TIGDAT.	2004/00/17 11:00
29	307	((photomask\$3 or photo-mask\$3 or mask\$3) near3 (type or kind or class	USPAT;	2004/09/17 11:00
		or (metal and (organic or polymer or resin or polyimide or phenolic or	US-PGPUB;	
]	]	acrylic)))) and (345/\$.ccls.)	ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
30	59	((photomask\$3 or photo-mask\$3 or mask\$3) with (metal and (organic or	USPAT;	2004/09/17 11:00
1	}	polymer or resin or polyimide or phenolic or acrylic))) and (345/\$.ccls.)	US-PGPUB;	
}	j		ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
31	1	(photomask\$3 or photo-mask\$3 or mask\$3) with (metal and (organic or	USPAT;	2004/09/17 12:31
		polymer or resin or polyimide or phenolic or acrylic)) with menu	US-PGPUB;	
			EPO; JPO;	1
	ļ		DERWENT;	,
	ļ		IBM_TDB	
41	8	3767490.URPN.	USPAT	2004/09/17 11:23
45	48	216/49.ccls. and 216/51.ccls.	USPAT;	2004/09/17 11:59
1			US-PGPUB;	
1	1		ЕРО; ЛРО;	
}	j		DERWENT,	
			IBM TDB	
46	1061	exposure with (ebeam or e-beam)	USPĀT;	2004/09/17 11:59
1			US-PGPUB;	
<b> </b>			ЕРО; ЛРО;	!
ļ			DERWENT;	
[			IBM TDB	
47	3002	exposure with (ebeam or e-beam or (energy near2 beam))	USPAT;	2004/09/17 12:31
1			US-PGPUB;	
(			ЕРО; ЈРО;	
1			DERWENT;	
Ì			IBM TDB	
48	361865	700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT;	2004/09/17 12:01
	301003	216/\$.ccls.	US-PGPUB;	200 110 3111 12.01
[			EPO; JPO;	
1	1		DERWENT;	
}			BM TDB	
49	556111	700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT;	2004/09/17 13:54
17	770111	216/\$.ccls. or 257/\$.ccls. or 438/\$.ccls. or 710/\$.ccls. or 430/\$.ccls. or 216/\$.ccls. or 257/\$.ccls.	_	2004/07/1/15:54
		ZEUTO-COLIS. OF ZETTO-COLIS.	US-PGPUB;	
1			EPO; JPO;	
}			DERWENT;	
L	L		IBM_TDB	

50	303	382/144.ccls.	USPAT;	2004/09/17 12:03
30		302/11/1000	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
		· · · · · · · · · · · · · · · · · · ·	IBM_TDB USPAT;	2004/09/17 13:00
51	20	382/144.ccls. and (organic or polymer or resin or polyimide or phenolic	US-PGPUB;	2004/03/17 13:00
		or acrylic)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
52	556260	(700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT;	2004/09/17 12:31
		216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
		71//0 1 420/0 1 - 71//0 1 420/0 ola on	IBM_TDB USPAT;	2004/09/17 12:31
53	1304	((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	US-PGPUB;	2004/09/17 12.31
		216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and (exposure with (ebeam	EPO; JPO;	
		or e-beam or (energy near2 beam)))	DERWENT;	
			IBM_TDB	
54	77	(((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT;	2004/09/17 12:58
		216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and (exposure with (ebeam	US-PGPUB;	
		or e-beam or (energy near2 beam)))) and ((photomask\$3 or	EPO; JPO;	
		photo-mask\$3 or mask\$3) with (metal and (organic or polymer or resin	DERWENT;	
		or polyimide or phenolic or acrylic)))	IBM_TDB USPAT;	2004/09/17 13:50
55	318	((photomask\$3 or photo-mask\$3) near3 ((first and second) or	US-PGPUB;	2004/09/17 13.30
		another)).clm.	EPO; JPO;	
			DERWENT;	
Ì			IBM_TDB	
56	261	((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPĀT;	2004/09/17 12:59
		216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and (((photomask\$3 or	US-PGPUB;	
	ļ	photo-mask\$3) near3 ((first and second) or another)).clm.)	ЕРО; ЈРО;	
			DERWENT;	
		((month) 1	IBM_TDB USPAT;	2004/09/17 13:51
57	82	(((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or 216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and (((photomask\$3 or	US-PGPUB;	2004/07/17 13.51
		photo-mask\$3) near3 ((first and second) or another)).clm.)) and (organic	EPO; JPO;	
1		or resin or polyimide or phenolic or acrylic)	DERWENT;	
		of residual of polyment of providing the providing the polyment of	IBM_TDB	
58	2818	(photomask\$3 or photo-mask\$3 or mask\$3) with ((mass adj2 (produc\$4	USPAT;	2004/09/17 13:54
		or manufactur\$4 or fabricat\$4 or making)) or batch or lot)	US-PGPUB;	
			EPO; JPO;	
	1		DERWENT; IBM TDB	
50	286006	((organic or resin or polyimide or phenolic or acrylic) with	USPAT;	2004/09/17 15:35
59	280000	((organic of resh of polynthue of photonic of actylic) with (photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6	US-PGPUB;	200 1103711 1212
		or photolithograph\$6 or expos\$4 or radiation or UV or EUV or shield\$4	EPO; JPO;	
	1	or block\$4 or sheild\$4))	DERWENT;	
	,	"	IBM_TDB	
60	310		USPAT;	2004/09/17 14:22
		subsequent or after) with ((mass adj2 (produc\$4 or manufactur\$4 or	US-PGPUB;	
		fabricat\$4 or making)) or batch or lot)	EPO; JPO; DERWENT;	
			IBM TDB	
61	33	(((organic or resin or polyimide or phenolic or acrylic) with	USPAT;	2004/09/17 14:03
01	33	((hotosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6	US-PGPUB;	
		or photolithograph\$6 or expos\$4 or radiation or UV or EUV or shield\$4	ЕРО; ЈРО;	
		or block\$4 or sheild\$4))) and ((photomask\$3 or photo-mask\$3 or	DERWENT;	
		mask\$3) with (before or prior or subsequent or after) with ((mass adj2	IBM_TDB	
		(produc\$4 or manufactur\$4 or fabricat\$4 or making)) or batch or lot))		<u></u>

52	14 (		USPAT;	2004/09/17 13:54
3 <b>2</b>	2	216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and ((((organic or restriction))) or acrylic) with (photosensit\$5 or photolacquer or	US-PGPUB; EPO; JPO; DERWENT;	
	ı	radiation or UV or EUV or shield\$4 or block\$4 or shelld\$4))) and ((photomask\$3 or photo-mask\$3 or mask\$3) with (before or prior or	IBM_TDB	
63	10 /	subsequent or after) with ((mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) or batch or lot))) ((((organic or resin or polyimide or phenolic or acrylic) with	USPAT;	2004/09/17 14:14
		(photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or expos\$4 or radiation or UV or EUV or shield\$4 or block\$4 or sheild\$4))) and ((photomask\$3 or photo-mask\$3 or mask\$3) with (before or prior or subsequent or after) with ((mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) or batch or lot))) not (((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or 216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	
		((((organic or resin or polyimide or phenolic or acrylic) with (photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or expos\$4 or radiation or UV or EUV or shield\$4 or block\$4 or sheild\$4))) and ((photomask\$3 or photo-mask\$3 or mask\$3) with (before or prior or subsequent or after) with ((mass adj2	·	
65		(produc\$4 or manufactur\$4 or fabricat\$4 or making)) or batch or lot)))) (photomask\$3 or photo-mask\$3 or mask\$3) with ((batch or lot) near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/17 15:27
66	1119	(photomask\$3 or photo-mask\$3 or mask\$3) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/09/17 15:33
68	1374	((photomask\$3 or photo-mask\$3 or mask\$3) with ((batch or lot) near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making))) or ((photomask\$3 or photo-mask\$3 or mask\$3) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/17 14:26
69	181	(((organic or resin or polyimide or phenolic or acrylic) with (photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or expos\$4 or radiation or UV or EUV or shield\$4 or block\$4 or sheild\$4))) and (((photomask\$3 or photo-mask\$3 or mask\$3) with ((batch or lot) near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making))) or ((photomask\$3 or photo-mask\$3 or mask\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/17 14:37
70	91	with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)))) ((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or 216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and ((((organic or resin or polyimide or phenolic or acrylic) with (photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or expos\$4 or radiation or UV or EUV or shield\$4 or block\$4 or sheild\$4))) and (((photomask\$3 or photo-mask\$3 or mask\$3) with ((batch or lot) near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making))) or ((photomask\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/17 14:37
71	321694	or photo-mask\$3 or mask\$3) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	

72	172	(((organic or resin or polyimide or phenolic or acrylic) with	USPAT;	2004/09/17 14:37
12	1/2	(((organic or resin or polynthide of phenolic of activity) with (photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or light or UV or EUV or shield\$4 or block\$4 or	US-PGPUB; EPO; JPO;	
		sheild\$4 or phototool\$3 or photo-tool\$3))) and (((photomask\$3 or	DERWENT;	
		photo-mask\$3 or mask\$3) with ((batch or lot) near2 (produc\$4 or	IBM_TDB	
		manufactur\$4 or fabricat\$4 or making))) or ((photomask\$3 or photo-mask\$3 or mask\$3) with (mass adj2 (produc\$4 or manufactur\$4		
		or fabricat\$4 or making))))		·
73	81	((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT;	2004/09/17 14:37
		216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and ((((organic or resin or polyimide or phenolic or acrylic) with (photosensit\$5 or photolacquer or	US-PGPUB; EPO; JPO;	
		photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or light or UV	DERWENT;	
		or EUV or shield\$4 or block\$4 or sheild\$4 or phototool\$3 or	IBM_TDB	
		photo-tool\$3))) and (((photomask\$3 or photo-mask\$3 or mask\$3) with ((batch or lot) near2 (produc\$4 or manufactur\$4 or fabricat\$4 or		
		making))) or ((photomask\$3 or photo-mask\$3 or mask\$3) with (mass		
74	2	adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making))))) 20020042007.pn.	USPAT;	2004/09/17 15:21
14	2	20020042007.pm.	US-PGPUB;	200 1103717 13.21
			EPO; JPO;	
			DERWENT; IBM_TDB	
76	5033	(before or prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or	USPAT;	2004/09/17 15:45
		manufactur\$4 or fabricat\$4 or process\$3))	US-PGPUB; EPO; JPO;	
			DERWENT;	
			IBM_TDB	
77	5007	(before or prior or subsequent\$2) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or process\$3))	USPAT; US-PGPUB;	2004/09/17 15:44
		manufacture of rabificates of processes))	ЕРО; ЛРО;	
		,	DERWENT;	
78	10005	((before or prior or subsequent\$2) with ((batch or lot) near2 (produc\$4	IBM_TDB USPAT;	2004/09/17 15:34
, 0	10003	or manufactur\$4 or fabricat\$4 or process\$3))) or ((before or prior or	US-PGPUB;	
		subsequent\$2) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or process\$3)))	EPO; JPO; DERWENT;	
		or process <sub>3</sub> 3)))	IBM_TDB	
79	3	(((before or prior or subsequent\$2) with ((batch or lot) near2 (produc\$4	USPAT;	2004/09/17 15:46
		or manufactur\$4 or fabricat\$4 or process\$3))) or ((before or prior or subsequent\$2) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4	US-PGPUB; EPO; JPO;	
		or process\$3)))) and ((organic or resin or polyimide or phenolic or	DERWENT;	
	ļ	acrylic) with (photomask\$3 or photo-mask\$3) with (block\$4 or sheild\$3 or sheild\$3 or attenuat\$4 or absorb\$4))	IBM_TDB	
80	23	(((before or prior or subsequent\$2) with ((batch or lot) near2 (produc\$4	USPAT;	2004/09/17 15:39
		or manufactur\$4 or fabricat\$4 or process\$3))) or ((before or prior or	US-PGPUB;	
		subsequent\$2) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or process\$3)))) and ((organic or resin or polyimide or phenolic or	EPO; JPO; DERWENT;	
		acrylic) with mask\$3 with (photosensit\$5 or photolacquer or	IBM_TDB	
		photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or UV or		
81	51	EUV or shield\$4 or block\$4 or sheild\$4 or attenuat\$4 or absorb\$4)) (before or prior or subsequent\$2) with (mass adj2 (produc\$4 or	USPAT;	2004/09/17 15:45
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	US-PGPUB,	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist)	EPO; JPO; DERWENT;	
			IBM_TDB	
82	42	(before or prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or	USPAT;	2004/09/17 15:45
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or photo-mask\$3 or mask\$3 or photo-resist)	US-PGPUB; EPO; JPO;	
		r	DERWENT;	
			IBM_TDB	

	02	(A-fine major or subgroupent(2) with (mass edi2 (produc(4 or	USPAT;	2004/09/17 15:45
83	93	((before or prior or subsequent\$2) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or photo-mask\$3 or mask\$3 or photoresist or photo-resist)) or ((before or	US-PGPUB; EPO; JPO;	200 HONET 13.73
		prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or	DERWENT;	
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	IBM_TDB	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist))		
34	23	(((before or prior or subsequent\$2) with (mass adj2 (produc\$4 or	USPAT;	2004/09/17 15:46
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	US-PGPUB;	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist)) or ((before or	EPO; JPO;	
		prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or	DERWENT; IBM_TDB	
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or photo-mask\$3 or mask\$3 or photoresist or photo-resist))) and (organic or	IDM_IDD	
		resin or polyimide or phenolic or acrylic)		
5	14	((((before or prior or subsequent\$2) with (mass adj2 (produc\$4 or	USPAT;	2004/09/17 15:51
5	17	manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	US-PGPUB;	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist)) or ((before or	ЕРО; ЈРО;	
		prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or	DERWENT;	
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	IBM_TDB	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist))) and (organic or		
		resin or polyimide or phenolic or acrylic)) and ((700/\$.ccls. or		
		702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or 216/\$.ccls. or		
36	0	257/\$.ccls.) or 382/144.ccls.) (((((before or prior or subsequent\$2) with (mass adj2 (produc\$4 or	USPAT;	2004/09/17 15:51
U	"	manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	US-PGPUB;	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist)) or ((before or	ЕРО; ЛРО;	
		prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or	DERWENT;	
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	IBM_TDB	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist))) and (organic or		
		resin or polyimide or phenolic or acrylic)) and ((700/\$.ccls. or		
		702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or 216/\$.ccls. or		
		257/\$.ccls.) or 382/144.ccls.)) not ((((before or prior or subsequent\$2) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or process\$3))		
		with (mass adj2 (produc\$4 of manufactur\$4 of labificat\$4 of process\$5)) with (photomask\$3 or photo-mask\$3 or mask\$3 or photoresist or		
		photo-resist)) or ((before or prior or subsequent\$2) with ((batch or lot)		
		near2 (produc\$4 or manufactur\$4 or fabricat\$4 or process\$3)) with		
		(photomask\$3 or photo-mask\$3 or mask\$3 or photoresist or		
	Ì	photo-resist))) and (organic or resin or polyimide or phenolic or acrylic))		
87	9	((((before or prior or subsequent\$2) with (mass adj2 (produc\$4 or	USPAT;	2004/09/17 15:51
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	US-PGPUB;	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist)) or ((before or	EPO; JPO; DERWENT;	
		prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	IBM_TDB	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist))) and (organic or	IDIII_122	
		resin or polyimide or phenolic or acrylic)) not (((((before or prior or		
		subsequent\$2) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4		
		or process\$3)) with (photomask\$3 or photo-mask\$3 or mask\$3 or		
		photoresist or photo-resist)) or ((before or prior or subsequent\$2) with		
		((batch or lot) near2 (produc\$4 or manufactur\$4 or fabricat\$4 or		
		process\$3)) with (photomask\$3 or photo-mask\$3 or mask\$3 or		
		photoresist or photo-resist))) and (organic or resin or polyimide or phenolic or acrylic)) and ((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or		
		716/\$.ccls. or 430/\$.ccls. or 216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.))		
	1	20020042007.pn. and Rom and logic and cell	USPAT;	2004/08/31 20:30
-	1	200200 12007.pm. and from and toget and von	US-PGPUB;	
		·	ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	2004/00/21 20 5
	1 1	20020042007.pn. and Rom and logic and (unit near2 cell)	USPAT;	2004/08/31 20:54
-	1		TIO DODITIO	
-	1		US-PGPUB;	
-	1		US-PGPUB; EPO; JPO; DERWENT;	

			Trop .	
-	1	20020042007.pn. and photomask\$3 with amount	USPAT,	2004/08/31 20:54
	}		US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
	1		IBM_TDB	1
_	1	20020042007.pn. and (photomask\$3 with amount)	USPAT;	2004/08/31 20:55
	,		US-PGPUB;	
			EPO; JPO;	
	1		DERWENT;	
1	1		IBM_TDB	
	1	20020042007 pp. and (averager \$2 with amount)	USPAT;	2004/08/31 21:03
-	1	20020042007.pn. and (exposur\$3 with amount)	US-PGPUB;	2004/08/31 21.03
			EDO: TOO	
	[		EPO; JPO;	
	}		DERWENT;	
	1		IBM_TDB	
-	1	20020042007.pn. and ((exposur\$3 or photomask\$3) with (amount or	USPAT;	2004/08/31 21:04
	1	[ jud\$6))	US-PGPUB;	
1	1		EPO; JPO;	
1	-		DERWENT;	
	ļ		IBM_TDB	·
-	1	20020042007.pn. and ((exposur\$3 or photomask\$3) with (amount or	USPAT;	2004/08/31 21:04
	[	judg\$6))	US-PGPUB;	
1	Ì	J44844))	ЕРО; ЛРО;	
	1		DERWENT;	
}			IBM_TDB	}
	1	20020042007 mg and ((a)magurf2 or photomoglf2) same (amount or		2004/09/21 22:19
_	1	20020042007.pn. and ((exposur\$3 or photomask\$3) same (amount or	USPAT;	2004/08/31 22:18
	Ì	judg\$6))	US-PGPUB;	
j			ЕРО; ЈРО;	
j	j		DERWENT;	
			IBM_TDB	
-	1	20020042007.pn. and (prior).clm.	USPAT;	2004/08/31 21:52
			US-PGPUB;	
j	ļ		ЕРО; ЛРО;	ļ
			DERWENT;	
			IBM_TDB	{
_	1	20020042007.pn. and (prior)	USPAT;	2004/08/31 21:52
	1	200200 1200 r.ph. ana (prior)	US-PGPUB;	200 1100/31 21:32
			EPO; JPO;	
			DERWENT;	
	,	20020042007 and (notte	IBM_TDB	2004/09/21 22:20
-	1	20020042007.pn. and (pattern\$4 with logic)	USPAT;	2004/08/31 22:20
1			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
	Ì		IBM_TDB	
-	1	20020042007.pn. and (pattern\$4 same logic)	USPAT;	2004/08/31 22:24
	ļ		US-PGPUB;	[
			ЕРО; ЈРО;	
	1		DERWENT,	
			IBM_TDB	
-	1	20020042007.pn. and (pattern\$4 same ROM)	USPAT;	2004/08/31 22:26
	,		US-PGPUB;	
	ļ		EPO; JPO;	[
			DERWENT;	
	1		1	
		20020042002	IBM_TDB	2004/09/21 22 22
] -		20020042007.pn. and (menu same type)	USPAT;	2004/08/31 22:26
			US-PGPUB;	
			ЕРО, ЈРО,	
			DERWENT,	
	ļ		IBM_TDB	

-	1	20020042007.pn. and (energy near3 beam)	USPAT;	2004/08/31 22:27
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
l _	1 1	20020042007.pn. and (evaluat\$4 same predetermin\$7 same pattern\$4)	USPAT;	2004/08/31 22:30
	•	200200 (200), pri. drid (a variation ) contra pro-	US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM TDB	
		20070042007		2004/09/21 22:20
-	1	20020042007.pn. and (reproduc\$5)	USPAT;	2004/08/31 22:29
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	1	20020042007.pn. and (differ\$8 same region\$4)	USPAT;	2004/08/31 22:29
		-	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
_	1	20020042007.pn. and (evaluat\$4 same quality same pattern\$4)	USPAT;	2004/08/31 22:30
	1	20020042007.pit. and (evaluate) barne quartey barne patterns sy	US-PGPUB;	200 11 00/01 22/00
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	2004/00/01 22:20
-	2	20020042007.pn.	USPAT;	2004/09/01 22:38
		,	US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
_	1	20020042007.pn. and mass.clm.	USPAT;	2004/09/01 23:01
		•	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
	1 1	20020042007.pn. and prior	USPAT;	2004/09/01 23:08
	1	20020042007.pii. and prior	US-PGPUB;	200 1103701 23.00
			EPO; JPO;	
			DERWENT;	
		DOM AL	IBM_TDB	2004/00/01 23 00
1 -	3736	ROM near3 logic	USPAT;	2004/09/01 23:08
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
-	2193	ROM near2 logic	USPAT;	2004/09/01 23:10
	1		US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
_	463	ROM near2 (logic near2 circuit)	USPAT;	2004/09/01 23:10
		Trong (10010 Hamp arrange)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	2004/00/15 01 15
-	1	20020042007.pn. and (product\$4 near4 amount)	USPAT;	2004/09/16 01:15
	1		US-PGPUB;	
1			ЕРО; ЈРО;	
1			DERWENT;	
			IBM_TDB	

-	2	20020042007.pn.	USPAT;	2004/09/15 23:33
1			US-PGPUB; EPO; JPO;	
			DERWENT;	
1	1		IBM_TDB	
-	684	organic with (photomask\$3 or photo-mask\$3)	USPAT;	2004/09/16 00:24
	1	D == (1)	US-PGPUB;	
}			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
-	700	(mass near2 production) with (exposure or lithography)	USPAT;	2004/09/16 00:36
ì			US-PGPUB;	
			ЕРО; ЈРО;	
	1		DERWENT;	
			IBM_TDB	2004/00/14 00 24
-	5	((mass near2 production) with (exposure or lithography)) and	USPAT;	2004/09/16 00:26
}	1	(700/121.ccls.)	US-PGPUB;	
			EPO; JPO; DERWENT;	
Ì	1		IBM_TDB	
_	355	organic\$4 with (photomask\$3 or photo-mask\$3 or mask\$3) with resin	USPAT;	2004/09/16 00:52
		with (photo or EUV or UV or ultra-violet or light or lightsource or	US-PGPUB;	200 1100110 00.02
	1	photolithograph\$6 or photosensit\$6)	ЕРО; ЛРО;	
			DERWENT;	
			IBM TDB	
-	1	(organic\$4 with (photomask\$3 or photo-mask\$3 or mask\$3) with resin	USPĀT;	2004/09/16 00:48
		with (photo or EUV or UV or ultra-violet or light or lightsource or	US-PGPUB;	
j	]	photolithograph\$6 or photosensit\$6)) and (700/121.ccls.)	EPO; JPO;	
	1		DERWENT;	
ì			IBM_TDB	
-	138	(organic\$4 with (photomask\$3 or photo-mask\$3 or mask\$3) with resin	USPAT;	2004/09/16 00:34
		with (photo or EUV or UV or ultra-violet or light or lightsource or	US-PGPUB;	
1		photolithograph\$6 or photosensit\$6)) and (700/\$.ccls. or 702/\$.ccls. or	EPO; JPO;	
		438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls.)	DERWENT;	
j	1936	(maga mag-2 are duction) with (asmaguna an lithe arealy) on the termogle \$2	IBM_TDB USPAT;	2004/09/16 00:42
-	1930	(mass near2 production) with (exposure or lithography or photomask\$3 or photo-mask\$3 or resist or photo-resist or	US-PGPUB;	2004/09/10 00.42
		photolithograph\$6 or stepper)	EPO; JPO;	1
		protontinographics of stepper)	DERWENT;	
		,	IBM_TDB	
-	4	((organic\$4 with (photomask\$3 or photo-mask\$3 or mask\$3) with resin	USPĀT;	2004/09/16 00:46
		with (photo or EUV or UV or ultra-violet or light or lightsource or	US-PGPUB;	
		photolithograph\$6 or photosensit\$6)) and (700/\$,ccls. or 702/\$,ccls. or	ЕРО; ЈРО;	
		438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls.)) and ((mass near2 production)	DERWENT;	
		with (exposure or lithography or photomask\$3 or photo-mask\$3 or	IBM_TDB	
	2007	mask\$3 or resist or photo-resist or photolithograph\$6 or stepper))	Habar	
-	2805	(mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/16 00:46
		(exposure or lithograph\$6 or photomask\$3 or photo-mask\$3 or mask\$3	US-PGPUB;	}
		or resist or photo-resist or photolithograph\$6 or stepper or photo-lithograph\$6)	EPO; JPO; DERWENT;	
		phow-matographwo)	IBM_TDB	
_	2806	(mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/16 00:52
	2000	(exposur\$3 or lithograph\$6 or photomask\$3 or photo-mask\$3	US-PGPUB;	200-1107/10 00.52
		or resist or photo-resist or photolithograph\$6 or stepper or	EPO; JPO;	
		photo-lithograph\$6)	DERWENT;	
			IBM_TDB	
-	8	((organic\$4 with (photomask\$3 or photo-mask\$3 or mask\$3) with resin	USPĀT;	2004/09/16 00:46
		with (photo or EUV or UV or ultra-violet or light or lightsource or	US-PGPUB;	
		photolithograph\$6 or photosensit\$6)) and (700/\$.ccls. or 702/\$.ccls. or	EPO; JPO;	
		438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls.)) and ((mass near2 (produc\$4 or	DERWENT;	
		manufactur\$4 or fabricat\$4 or making)) with (exposur\$3 or lithograph\$6	IBM_TDB	
		or photomask\$3 or photo-mask\$3 or mask\$3 or resist or photo-resist or		
L	L	photolithograph\$6 or stepper or photo-lithograph\$6))		

- 76 (mass nea (before or photo-mas or stepper	ar2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with 3 or lithograph\$6 or photomask\$3 or photo-mask\$3 or mask\$3 or photo-resist or photolithograph\$6 or stepper or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB;	2004/09/16 00:48
or resist of photo-lith  - 76 (mass nea (before or photo-mass or stepper)	rephoto-resist or photolithograph\$6 or stepper or or ograph\$6)) and (700/121.ccls.)  f2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with prior) with (exposur\$3 or lithograph\$6 or photomask\$3 or k\$3 or mask\$3 or resist or photo-resist or photolithograph\$6	EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB;	2004/09/16 00:56
- 76 (mass nea (before or photo-mas or stepper	ograph\$6)) and (700/121.ccls.)  (2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with prior) with (exposur\$3 or lithograph\$6 or photomask\$3 or k\$3 or mask\$3 or resist or photo-resist or photolithograph\$6	DERWENT; IBM_TDB USPAT; US-PGPUB;	2004/09/16 00:56
- 76 (mass nea (before or photo-mas or stepper	2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with prior) with (exposur\$3 or lithograph\$6 or photomask\$3 or k\$3 or mask\$3 or resist or photo-resist or photolithograph\$6	IBM_TDB USPAT; US-PGPUB;	2004/09/16 00:56
(before or photo-mas or stepper	prior) with (exposur\$3 or lithograph\$6 or photomask\$3 or k\$3 or mask\$3 or resist or photo-resist or photolithograph\$6	USPAT; US-PGPUB;	2004/09/16 00:56
(before or photo-mas or stepper	prior) with (exposur\$3 or lithograph\$6 or photomask\$3 or k\$3 or mask\$3 or resist or photo-resist or photolithograph\$6	US-PGPUB,	2004/09/16 00:56
photo-mas or stepper	k\$3 or mask\$3 or resist or photo-resist or photolithograph\$6	US-PGPUB;	
or stepper			
	or photo-lithograph\$6)	ЕРО; ЈРО;	
- 276315 photomasi	F	DERWENT;	
- 276315   photomasi		IBM_TDB	
	\$3 or photo-mask\$3 or photoresist or photo-resist or ((mask\$3	USPAT;	2004/09/16 01:31
or resist)	vith (photo or EUV or UV or ultra-violet or light or DUV or	US-PGPUB;	
excimer o	lightsource or photolithograph\$6 or photosensit\$6 or	ЕРО; ЈРО;	
photo-lith	ograph\$6 or positive or negative))	DERWENT;	
		IBM_TDB	
2 20020042	007.pn. and (organic\$6)	USPAT;	2004/09/16 01:17
		US-PGPUB;	
		ЕРО; ЈРО;	
		DERWENT,	
		IBM TDB	
9 ("468497)	" "5376483" "5378585" "5389474" "5418092" "5556724"	USPAT	2004/09/16 01:18
	"5989760" "5948572").pn.	OSIAI	2004/07/10 01.18
	th (photo or EUV or UV or ultra-violet or light or DUV or	USPAT;	2004/09/16 01:32
		US-PGPUB;	2004/05/10 01:32
	lightsource or photolithograph\$6 or photosensit\$6 or		
	ograph\$6 or positive or negative)) or photoresist) with	ЕРО; ЛРО;	
organic\$4	with resin	DERWENT;	
100	THE STATE OF THE S	IBM_TDB	
	ith (photo or EUV or UV or ultra-violet or light or DUV or	USPAT;	2004/09/16 01:39
	lightsource or photolithograph\$6 or photosensit\$6 or	US-PGPUB;	1
	ograph\$6 or positive or negative)) or photoresist) with	ЕРО; ЈРО;	
organic\$4	with resin) and @py<1985	DERWENT;	
		IBM_TDB	
	ith (photo or EUV or UV or ultra-violet or light or DUV or	USPAT;	2004/09/16 01:33
	lightsource or photolithograph\$6 or photosensit\$6 or	US-PGPUB,	
photo-lith	ograph\$6 or positive or negative)) or photoresist) with	ЕРО; ЛРО;	
organic\$4	with resin).clm.	DERWENT,	
		IBM_TDB	
- 14 ((((resist	with (photo or EUV or UV or ultra-violet or light or DUV or	USPAT;	2004/09/16 01:38
excimer o	lightsource or photolithograph\$6 or photosensit\$6 or	US-PGPUB;	1
	ograph\$6 or positive or negative)) or photoresist) with	ЕРО; ЛРО;	
	with resin) and @py<1985) and ((((resist with (photo or EUV	DERWENT;	
or UV or	iltra-violet or light or DUV or excimer or lightsource or	IBM_TDB	
	graph\$6 or photosensit\$6 or photo-lithograph\$6 or positive or		
	or photoresist) with organic\$4 with resin).clm.)		
	t near2 metal	USPAT;	2004/09/16 01:39
	V ALTURE SALVINE	US-PGPUB;	200-707/1001.37
		EPO; JPO;	
		DERWENT;	
200 /.1	at many mataly also	IBM_TDB	2004/00/17 01 20
- 680 (photoresi	st near2 metal).clm.	USPAT;	2004/09/16 01:39
		US-PGPUB;	
		ЕРО; ЈРО;	
		DERWENT;	
		IBM_TDB	3
- 75 ((photores	ist near2 metal).clm.) and @py<1985	USPAT;	2004/09/16 14:41
		US-PGPUB;	
		ЕРО; ЈРО;	
		DERWENT;	1
		IBM_TDB	

-	0	20020042007.pn. and (Rom same logic same cell)	USPAT;	2004/09/16 19:26
		• •	US-PGPUB,	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	,
-	1	5965306.pn. and (mass with production)	USPAT;	2004/09/16 20:44
			US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
-	2	5965306.pn.	USPAT;	2004/09/16 20:44
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
-	2241	(mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/16 21:26
		(deposit\$4 or anneal\$5)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	